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a poly((meth)acrylic acid)-based water-soluble photo-sensitive resin (A) having an acid value of 150 mgKOH/g or more on a solid basis;

$$\begin{array}{c} \text{O} \\ \parallel \\ \text{H}_2\text{C}=\text{C}-\text{C}-\text{O}-\text{R}^2-\text{O}-\text{C}(\text{H}_2)-\text{CH}-\text{CH}_2 \\ | \\ \text{R}^1 \end{array} \quad \begin{array}{c} \diagup \\ \diagdown \\ \text{O} \end{array} \quad (1)$$

a photopolymerization initiator (B); and
water (C).

2. A photosensitive resin composition according to claim 1, wherein the carboxyl groups of the ((meth)acrylic acid)-based polymer to which the compound represented by formula (1) has not been added are partially or entirely neutralized with an alkali.

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Statement under Article 19(1)

In amended claim 1, the acid value has been clarified to be 170 mgKOH/g or more on a solid basis.

Each of added claims 4 and 5 claims a hydrogel formed through the method as recited in claim 3.